

ABSTRACT OF THE DISCLOSURE

A semiconductor device with an enhanced registration accuracy photo-mask used for manufacturing the device and a registration accuracy enhancement method are provided, by detecting lens aberration which
5 causes problems in the process of manufacturing a semiconductor device. The semiconductor device includes an auxiliary mark including an inner mark having stepped portions with four sides as stepped portions to be detected and an outer mark having stepped portion as stepped portions to be detected, provided approximately parallel to stepped portions along four
10 sides of the inner mark.